

Supplemental Document

Atomic Layer Deposition of Silver Halides

Georgi Popov*, Timo Hatanpää, Alexander Weiß, Mykhailo Chundak, Mikko Ritala, Marianna Kemell

Department of Chemistry, University of Helsinki, P.O. Box 55, FI-00014 Helsinki, Finland

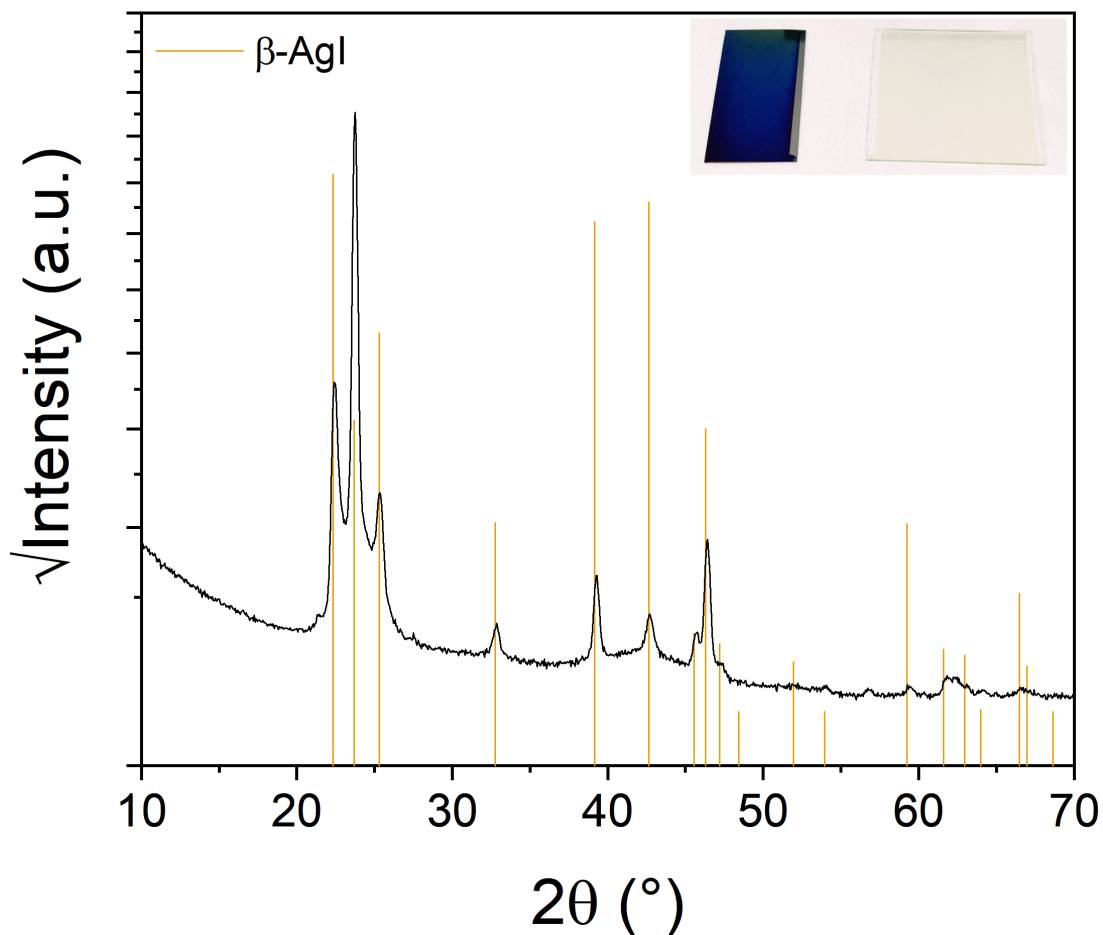


Figure 1. X-ray diffraction pattern of an AgI film deposited at 100 °C with 1000 cycles of 1.0 s Ag(FOD)(PEt₃) and SnI₄ precursor pulses separated by 1.0 s purges. The reference β-AgI pattern is from COD entry 1529745. The inset shows a photograph of the same film on the Si and glass substrates.